

Amendments to the Specification

Please replace paragraph [0045] with the following amended paragraph:

a1
“Referring now to Fig. 4D, a passivation layer 45 is then formed over the exposed surfaces of the first substrate, including over the data pattern. That passivation layer is beneficially comprised of an organic material such as acryl, BCB (benzocyclobutene), or the like, or an inorganic material such as silicon nitride, silicon oxide, or the like. A contact hole 47 is then formed by selectively removing a portion of the passivation layer [[47]] 45 so as to expose a portion of the drain electrode 43e. Additionally, the passivation layer [[47]] 45 is removed from over the gate pad and the data pad.”
